

a carrier which transfers the process substrates, the portion of the dummy substrates and said one or more dummy substrates to the boat; and

a cleaning gas line which introduces a cleaning gas into the reaction chamber to thereby clean said one or more dummy substrates within the reaction chamber.

2(Amended). The apparatus as recited in claim 1, further comprising a counter which counts the number of usages in batch-processing of each dummy substrate stored in the stocker and wherein the number of usages of said one or more dummy substrates is not greater than a predetermined number.

A1
3(Amended). The apparatus as recited in claim 1, wherein all the dummy substrates stored in the stocker are simultaneously cleaned in the reaction chamber.

6(Amended). The apparatus as recited in claim 1, wherein the boat is simultaneously cleaned while cleaning the dummy substrates.

A2
7(Amended). The apparatus as recited in claim 6, wherein the reaction chamber is simultaneously cleaned while cleaning the dummy substrates.

8(Amended). The apparatus as recited in claim 1, wherein the boat is a quartz boat which accommodates a predetermined number of substrates.

Please cancel claims 9-12 without prejudice or disclaimer and add the following new claims to the application.

A3
13(New). A substrate processing apparatus, comprising:

a processing chamber;

a boat which loads a plurality of substrates into the processing chamber;

a stocker which stores at least dummy substrates loaded into the processing chamber together with substrates to be used for processing semiconductor products, when the substrate are carried out process except cleaning process;

a transfer device for transferring the dummy substrates stored in the stoker between the boat and the stocker; and

a cleaning gas line which supplies a cleaning gas into the processing chamber in order to clean the dummy substrates while the dummy substrates are held in the processing chamber.

14(New). The apparatus as recited in claim 13, further comprising a counter which counts the number of usages of each dummy substrate stored in the stocker and determines whether said each dummy substrate reached a predetermined usage limit or not and

wherein one or more dummy substrates determined as reaching the predetermined usage limit are transferred from the stocker to the boat by the transfer device and the cleaning gas line supplies the cleaning gas into the processing chamber in order to clean said one or more dummy substrates while said one or more dummy substrates are held in the processing chamber.

A3
15(New). The apparatus as recited in claim 13, wherein all the dummy substrates stored in the stocker are simultaneously cleaned in the processing chamber.

16(New). The apparatus as recited in claim 13, wherein the substrates and the dummy substrates are silicon wafers and quartz wafers, respectively.

17(New). The apparatus as recited in claim 13, wherein the substrates and the dummy substrates are silicon wafers and alumina coated silicon wafers on top and bottom surfaces thereof, respectively.

18(New). The apparatus as recited in claim 13, wherein the boat is simultaneously cleaned while cleaning the dummy substrates.

19(New). The apparatus as recited in claim 18, wherein the processing chamber is simultaneously cleaned while cleaning the dummy substrates.

20(New). The apparatus as recited in claim 13, wherein the boat is a quartz boat which accommodates a predetermined number of substrates.

21(New). The apparatus as recited in claim 20, wherein the ratio of the number of said portion of the dummy substrates to that of the substrates is fixed and the capacity of the stocker is n times the number of said portion of the dummy substrates, n being a positive integer.

22(New). A substrate processing apparatus, comprising:

a processing chamber;

M2
a substrate support which supports in the processing chamber at least one of substrate to be used for producing semiconductor products or at least one of dummy substrate;

a stocker which stores the dummy substrate;

a transfer device which transfers to the substrate support the substrate to be used for producing the semiconductor products which is/are processed in the processing chamber and transfers between the substrate support and the stocker the dummy substrate which is/are processed in the chamber; and

a cleaning gas line which supply a cleaning gas into the processing chamber while the dummy substrates which have been processed in the processing chamber are supported by the substrate support in the processing chamber.